
**Optics and photonics — Preparation
of drawings for optical elements and
systems —**

**Part 8:
Surface texture**

*Optique et photonique — Indications sur les dessins pour éléments et
systèmes optiques —*

Partie 8: État de surface

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ISO copyright office
CP 401 • Ch. de Blandonnet 8
CH-1214 Vernier, Geneva
Phone: +41 22 749 01 11
Fax: +41 22 749 09 47
Email: copyright@iso.org
Website: www.iso.org

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Contents

Page

Foreword	iv
1 Scope	1
2 Normative references	1
3 Terms and definitions	1
4 Description of surface texture	7
4.1 General	7
4.2 Description of matt surfaces	8
4.3 Description of optically smooth surfaces	8
4.3.1 Description methods	8
4.3.2 Rms roughness and rms waviness	8
4.3.3 Polish grades	9
4.3.4 Power spectral density (PSD) function	9
4.3.5 Area power spectral density (APSD) function	10
4.3.6 Rms slope	11
4.3.7 Area rms slope	11
5 Indication in drawings	11
5.1 General	11
5.2 Indication for matt surface texture	11
5.3 Indication for optically smooth surface texture	12
5.3.1 Optically smooth surface without quantitative modification	12
5.3.2 Indication of smoothness by polish grade	12
5.3.3 Indication of rms roughness and rms waviness	13
5.3.4 Indication of PSD function specification	13
5.3.5 Indication of APSD function specification	13
5.3.6 Indication of rms or area rms slope specification	14
5.3.7 Indication of lay	14
5.4 Location	15
Annex A (informative) Relationship between surface texture and scattering characteristic of textured surfaces	16
Annex B (informative) Examples of indication of surface texture requirements	18
Bibliography	22

Foreword

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This document was prepared by Technical Committee ISO/TC 172, *Optics and Photonics*, Subcommittee SC 1, *Fundamental Standards*.

This third edition cancels and replaces the second edition (ISO 10110-8:2010), which has been technically revised.

The main changes compared to the previous edition are as follows:

- a) a drawing notation and interpretation is provided for the following additional areal terms: S_a , S_q , $S\Delta q$, and APSD;
- b) the following terms are explicitly allowed: R_a , R_{sk} , R_{ku} , and ACV , which also required the addition of more definitions, and additional examples.
- c) this edition removes the reference to micro-defects as a method of determining polish grade, and replaces it with specific rms roughness values.

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